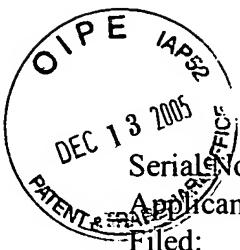


12-14-05

JFW



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Serial No.: 10/676,983
Applicant: Tingkai Li *et al.*
Filed: September 30, 2003
Group #: 1765
Examiner: Lan Vinh

Confirmation Number: 7693

Docket No: SLA.0785
Customer No: 55376
For: Selective Etching Processes for In_2O_3 Thin Films in FeRAM Device Applications

MS AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

RESPONSE TO OFFICE ACTION UNDER 37 C.F.R. § 1.111
Change of Correspondence Address
Introductory Comments

In response to the Office Action dated September 14, 2005, please amend the above-identified Application as follows:

Amendment to the Specification None

Amendment to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Amendment to the Drawings None

Remarks/Arguments begin on page 7 of this paper.

An **Appendix** is not included.